

Status: 04/07/2017

● = Click here for website
○ = Service is provided, but website is not available

Service	Tools	SDU	CAU	Acreo	WUT	UL	UT	KTU
Semiconductor processing / microfabrication	Inductively Coupled Plasma Reactive Ion etching (ICP-RIE)	●		●				●
	Thin Film deposition	●		●			●	
	Pulsed laser deposition						●	
	Spin Coater	○		●				○
	HMDS Oven	○		●				
	Photoresist stripping, substrate surface cleaning			●				
	Plasma Cleaner	●		●		○		○
	Solvent Wet Bench	●		●				○
	Acid Wet Bench	●		●				○
	RCA Wet Bench	●		●				○
	Mask Aligner	●		●				●
	Dicing Saw	○		●				○
Thin film deposition	High resolution Sputter Coater	○		●		○		
	Spin coater			●				●
	Vacuum evaporation unit			●		○		●
	DLC synthesis system			●				●
	Microwave plasma enhanced chemical vapor deposition system			●		○		●
	RF reactive ion etching system			●				●
Thermal oxidation process	Oxide furnace			●				
Microdevices interfaces	Microdevices interfaces	○						
Computer simulation techniques		○		●				○
Growth of epitaxial layers on SiC-wafers	SiC epitaxy process (CVD reactor)			●				
SiC annealing process	Aviator			●				
Rapid thermal processing	Thermal process-RTA			●				
Nanofabrication	E-beam lithography	●						●
	Lithography-ALS stepper			●				
	Lithography-DSW stepper			●				
	Lithography-Mask production					○		
	Lithography-Mask aligner			●				
	Lloyd's mirror holographic lithography setup							●
	Universal optical spectroscopy and laser microfabrications system							●
SiC power device fabrication	Dry etching (ICP)			●				●
	Dry etching (RIE)			●				○
	Low Pressure Plasma Etcher			●				
Large-scale fabrication of solar cells	Roll-to-Roll production facility	○						
Prototyping of control systems for PE	Rapid Control Prototyping Platform				●			
Organic layers fabrication (solar cells)	Glovebox	○						
	Cleanroom	●		●			○ ^{1,2,3}	○ ¹

1 = ISO 5 2 = ISO 6 3 = ISO 8